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# **Laser-based Micro- and Nanoprocessing XII**

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*Editors*

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# Contents

vii	Authors
ix	Conference Committee

---

## SESSION 1 LASER MICRO STRUCTURING AND PROCESSING I

---

- 10520 03 **New laser slicing technology named KABRA process enables high speed and high efficiency SiC slicing (Invited Paper)** [10520-2]
- 10520 04 **Stealth Dicing technology with SWIR laser realizing high throughput Si wafer dicing** [10520-3]
- 10520 06 **Femtosecond laser direct writing of Cu-based fine patterns using Cu<sub>2</sub>O nanospheres** [10520-5]

---

## SESSION 2 LASER MICRO STRUCTURING AND PROCESSING II

---

- 10520 07 **Direct laser writing of 3D microfluidic structures in glass for lab-on-a-chip applications (Invited Paper)** [10520-6]
- 10520 0A **Incubation effect in burst mode fs-laser ablation of stainless steel samples** [10520-9]

---

## SESSION 3 LASER MICRO/NANO STRUCTURING ON FLEXIBLE SUBSTRATES

---

- 10520 0C **Nanoablation of Si surface with femtosecond-laser-induced plasmonic near-fields (Invited Paper)** [10520-11]
- 10520 0D **Direct observation of internal void formations in Stealth Dicing** [10520-12]
- 10520 0E **Solvent induced reversible deformations of polymeric 3D microstructures for actuation and sensing applications** [10520-13]
- 10520 0F **Flexible and stretchable micro GO/rGO optical structures by femtosecond laser photoreduction** [10520-14]

---

## SESSION 4 HIGH-SPEED LASER BEAM ENGINEERING SYSTEMS FOR HIGH-POWER, ULTRASHORT PULSED LASERS

---

- 10520 0G **Ultrafast dynamics of material excitation of dielectrics with ultrashort pulsed Bessel beams** [10520-16]

10520 OI      **Parallel processing of embossing dies with ultrafast lasers** [10520-18]

---

**SESSION 5      LARGE-AREA MICRO/NANO STRUCTURING AND LASER INTERFERENCE PATTERNING**

---

10520 OK      **Optimization for high speed surface processing of metallic surfaces utilizing direct laser interference patterning** [10520-21]

10520 OL      **2D laser induced periodic surface structures with double cross-polarized pulses** [10520-22]

10520 OM      **Double pulse explosion drilling of transparent materials** [10520-23]

---

**SESSION 6      DIRECT-WRITE PROCESSING, ABLATION, AND SURFACE MODIFICATION I**

---

10520 ON      **Applications of ultrafast laser direct writing: from polarization control to data storage (Invited Paper)** [10520-25]

10520 OP      **Laser direct writing of reduced graphene oxide micropatterns and sensor applications** [10520-27]

---

**SESSION 7      LASER MICRO/NANO STRUCTURING ON METALS**

---

10520 OR      **High repetition frequency micro hole drilling of metal foils using ultrashort pulse laser radiation** [10520-29]

10520 OS      **Characteristics of micro-holes drilled in ambient air and vacuum by high-power Nd:YAG laser** [10520-30]

10520 OV      **Formation of two-way shape memory effect in NiTi alloy using pulsed laser irradiation** [10520-32]

10520 OW      **Development of AISI 316L stainless steel coronary stent** [10520-33]

---

**SESSION 8      DIRECT-WRITE PROCESSING, ABLATION, AND SURFACE MODIFICATION II**

---

10520 OX      **New fast galvo scanner head for high throughput micromachining** [10520-34]

10520 OZ      **Microfabrication of curved sidewall grooves using scanning nanosecond excimer laser ablation** [10520-37]

10520 10      **Model for ultrafast laser micromachining** [10520-38]

---

**SESSION 9 ADVANCED 1D TO 3D SUBTRACTIVE AND ADDITIVE PROCESSES**

---

- 10520 13 **Direct writing of three-dimensional Cu-based sensors using femtosecond laser reduction of CuO nanoparticles (Invited Paper)** [10520-41]

---

**SESSION 10 ADVANCED LASER STRUCTURING FOR ENERGY STORAGE AND CONVERSION I**

---

- 10520 17 **Laser in battery manufacturing: impact of intrinsic and artificial electrode porosity on chemical degradation and battery lifetime** [10520-47]

---

**SESSION 11 ADVANCED LASER STRUCTURING FOR ENERGY STORAGE AND CONVERSION II**

---

- 10520 18 **Laser micro-spot welding of AISI 302 stainless steel sheets** [10520-48]

- 10520 19 **Modeling of a VMJ PV array under Gaussian high intensity laser power beam condition** [10520-49]

- 10520 1A **Glass light pipes for solar concentration** [10520-50]

---

**POSTER SESSION**

---

- 10520 1D **Laser interference lithography on non-planar surface for roll-to-roll process** [10520-24]

- 10520 1E **Improving piezo actuators for nanopositioning tasks** [10520-52]

- 10520 1G **Femtosecond laser-assisted etching: making arbitrary shaped 3D glass micro-structures** [10520-54]

- 10520 1J **Formation mechanism of self-assembled polarization-dependent periodic nanostructures in  $\beta$ - $\text{Ga}_2\text{O}_3$**  [10520-57]

- 10520 1K **Nano- and micro-structuring of fused silica using time-delay adjustable double flash ns-laser radiation** [10520-59]

- 10520 1M **Durable superhydrophobic-superoleophilic copper mesh fabricated by pulsed laser ablation for oil/water separation** [10520-61]

- 10520 1N **Three-dimensional micro-nano-hierarchical porous structures based on the deposition of the ablated material by picosecond pulses** [10520-62]

- 10520 1O **Pulsed laser micro-scribing of copper thin films on polyimide substrate in NaCl solution** [10520-63]

- 10520 1S **Dynamics of thermally generated microbubbles** [10520-67]
- 10520 1T **Laser pre-exposure to mitigate damage on microparticle-contaminated fused silica surface in high power laser systems** [10520-68]
- 10520 1V **Optimization of femtosecond laser micromachining of polylactide and PLLA/HAp composite** [10520-70]
- 10520 1W **Degradation of poly(L-lactide) under femtosecond laser treatment** [10520-71]
- 10520 1X **Experimental investigation of texturing complex geometry using high repetition nano laser and comparison with the simulated COMSOL model** [10520-72]
- 10520 1Y **Innovative approaches for coordinate extraction of curved shape and analyzing the effect of process parameters on the quality of the laser micro-machined surface** [10520-73]

# Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

- Abeywickrema, Ujitha, 1S  
Ancona, Antonio, 0A  
Antończak, Arkadiusz J., 1V, 1W  
Atkins, R., 1A  
Audouard, E., 10  
Banerjee, Partha, 1S  
Beresna, M., 0N  
Brambilla, G., 0N  
Brüning, Stephan, 0I  
Bruneel, D., 10  
Bude, Jeff D., 1T  
Cai, Jinguang, 0P  
Cangueiro, L., 10  
Carr, C. Wren, 1T  
Cedeño-Viveros, Luis D., 18  
Cheng, Ya, 07  
Choquet, Isabelle, 0A  
Cross, David, 1T  
Cui, Jingqin, 1M  
Dogan, Y., 1A  
Donko, A., 0N  
Du, Keming, 0I  
Duan, Wenqiang, 0S  
Ebrahimi Orimi, H., 1X, 1Y  
Ehrhardt, Martin, 1K  
Eom, Jeongsook, 19  
Er, Ali O., 0V  
Faucon, M., 0X  
Fraggelakis, F., 0L  
Gadonas, Roaldas, 1G  
Garcha, Raminder, 1T  
García-López, Erika, 0W, 18  
Gaudiuso, Caterina, 0A  
Gazińska, Małgorzata, 1W  
Gertus, T., 0N  
Giannuzzi, Giuseppe, 0A  
Gong, Jing, 0Z  
Götz, Bernt, 1E  
Gramov, Vassil, 1E  
Grigalevičiūtė, Giedrė, 1G  
Gruner, Andreas, 0R  
Gwak, Cheong Yeol, 1D  
Hagiya, Masato, 0C  
Han, Bing, 1K  
Hata, Seiichi, 06, 13  
Hirata, Kazuya, 03  
Hoffmann, Patrik, 0Z  
Hoffmann, Tim, 0K  
Holtum, T., 0G  
Hu, C., 1A  
Ilhom, Saidjafarzoda, 0V  
Infante, Daniel, 0Z  
Jagadeesh, S., 1X, 1Y  
Jarczynski, Manfred, 0I  
Je, Gyeongju, 1D  
Jenke, Gerald, 0I  
Jiang, Gedong, 1N  
Jing, Chengbin, 07  
Jonušauskas, Linas, 1G  
Kalupka, C., 0G  
Karaca, Haluk E., 0V  
Kholikov, Kholmukhodzha, 0V  
Kim, Gunzung, 19  
Kim, Young-Jin, 0F  
Kiyota, Hiroki, 04, 0D  
Kling, R., 0L, 0X  
Kondo, Yukinari, 06  
Kostro, André, 0Z  
Krishnan, Sivarama, 1O  
Kupisiewicz, A., 10  
Lang, Valentin, 0K  
Lasagni, Andrés Fabián, 0K  
Lee, Hyub, 0F  
Li, Kui, 1M  
Li, Peizhen, 0V  
Li, Xiaoguang, 1M  
Li, Xiaolong, 07  
Liao, Yang, 07  
Lim, Chin Huat Joel, 0F  
Lin, Jintian, 07  
Lin, Shengdong, 1M  
Loeschner, Udo, 0R  
Lopez, J., 0L, 0X  
Lorenz, Pierre, 1K  
Low, Mun Ji, 0F  
Lugarà, Pietro Mario, 0A  
Ma, Yong Won, 1D  
Madsen, C. K., 1A  
Malinauskas, Mangirdas, 0E  
Manek-Hönninger, Inka, 0L  
Martin, P. E., 10  
Mei, Xuesong, 0S, 1N  
Mincuzzi, G., 0L, 0X  
Mitra, Thomas, 0I  
Miura, K., 1J  
Miyaji, Godai, 0C  
Mizeikis, Vygaantas, 0E  
Mizoshiri, Mizue, 06, 13

Morrison, M., 1A  
Mottay, E., 10  
Murukeshan, Vadakke Matham, 0F  
Nagayama, N., 0M  
Nakanishi, Y., 1J  
Nammi, Srinagalakshmi, 1O  
Nara, Yasunaga, 04, 0D  
Narayanswamy, S., 1X, 1Y  
Narmontas, Andrius, 1G  
Nemickas, Gedvinas, 1G  
Nishio, T., 0M  
Norton, Mary A., 1T  
Paipulas, Domas, 0E  
Pan, Aifei, 1N  
Park, Jun Han, 1D  
Park, Yongwan, 19  
Pfleging, W., 17  
Purlys, Vytautas, 1G  
Raman, Rajesh N., 1T  
Ramos-de-Campos, J. A., 10  
Rebière, A., 0X  
Reininghaus, M., 0G  
Rekštýtė, Sima, 0E  
Roberts, Duvall, 0V  
Rodríguez, Ciro A., 0W, 18  
Sakakura, M., 1J  
Sakurai, Junpei, 06  
San, Omer, 0V  
Schille, Joerg, 0R  
Schüler, Andreas, 0Z  
Seeliger, Martin, 1E  
Seifert, H. J., 17  
Seyitliyev, Dovletgeldi, 0V  
Shen, Fei, 1M  
Shiby, Sooraj, 1O  
Shimizu, M., 1J  
Shimotsuma, Y., 1J  
Shin, Bo Sung, 1D  
Siller, Héctor R., 0W, 18  
Smyrek, P., 17  
Stępak, Bogusz D., 1V, 1W  
Suhara, H., 0M  
Szustakiewicz, Konrad, 1V, 1W  
Tamura, A., 0M  
Thomas, Zachary, 0V  
Tičkūnas, Titas, 1G  
Vasa, Nilesh J., 1O  
Vázquez, Elisa V., 18  
Violakis, Georgios, 0Z  
Wallace, Tylisia N., 1T  
Wang, Kedian, 0S  
Wang, Wenjun, 0S, 1N  
Watanabe, Akira, 0P  
Xu, Jian, 07  
Yun, Dan Hee, 1D  
Zagoranskiy, Igor, 1K  
Zhang, Guobiao, 1M  
Zhao, Chenglong, 1S  
Zhao, Xiongtao, 1K  
Zheng, Y., 17  
Zhong, Yi, 07  
Zhou, Rui, 1M  
Zimmer, Klaus, 1K

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- 4    High-speed Laser Beam Engineering Systems for High-power, Ultrashort Pulsed Lasers  
**Kunihiro Washio**, Paradigm Laser Research Ltd. (Japan)
- 5    Large-area Micro/Nano Structuring and Laser Interference Patterning  
**Andrés-Fabián Lasagni**, TU Dresden (Germany)
- 6    Direct-write Processing, Ablation, and Surface Modification I  
**Barbara Stadlober**, JOANNEUM RESEARCH Forschungsgesellschaft mbH (Austria)
- 7    Laser Micro/Nano Structuring on Metals  
**Miguel Holgado Bolaños**, Universidad Politécnica de Madrid (Spain)
- 8    Direct-write Processing, Ablation, and Surface Modification II  
**Antonio Ancona**, CNR-Istituto di Fotonica e Nanotecnologie (Italy)
- 9    Advanced 1D to 3D Subtractive and Additive Processes  
**Xianfan Xu**, Purdue University (United States)
- 10   Advanced Laser Structuring for Energy Storage and Conversion I  
**Wilhelm Pfleiderer**, Karlsruher Institut für Technologie (Germany)

- 11 Advanced Laser Structuring for Energy Storage and Conversion II  
**Haibin Zhang**, Electro Scientific Industries, Inc. (United States)

